

Foreword

It is really a great pleasure to write the foreword for this special issue on the “Phase Stability, Phase Transformation, and Reactive Phase Formation in Electronic Materials VII” symposium. This special issue contains peer-reviewed papers from those presented at the TMS Annual Meeting held from March 9th to 13th, 2008 in New Orleans, LA. This symposium addressed the stability, transformation, and formation of phases during the fabrication, processing, and utilization of electronic materials and devices. Comprising 48 oral presentations from 11 countries, there is no doubt that the internationalized term “phase” (相, 상, そう, фаза, fase, faza) is the key word. When this symposium was first introduced 7 years ago, it did not occur to the organizers that this symposium would run for seven consecutive years, and more amazingly it is still going strong for the next year in San Francisco. The organizers acknowledge all the efforts of authors and reviewers for making this special issue possible. Readers should find the manuscripts technologically valuable and of great scientific interest.

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